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	306794	P-0388.010-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: BAKKER et al.	
Appl. No.: TO BE ASSIGNED	
Filing Date: November 21, 2003	
Examiner:	Group Art Unit:

Date: November 21, 2003 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR					
	BR					
	CR					
	DR					
	ER					
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	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					
	OR					

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	Abstract		Readily Available	
						Enclosed	No	Enclose	No
HN	PR	EP 1 182 510 A1	02/2002	Europe	MOORS et al.	X			
	QR								
	RR								
	SR								
	TR								
	UR								
	VR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

HN	WR	Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," J. Vac. Sci. Technol. B 12(6):3833-3840, XP-002096163 (1994)				
	XR					
	YR					
	ZR					
	AAR					
	BBR					
	CCR					

Examiner H. Nguyen Date Considered: 8/4/2004

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.